## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF:

Jamal RAMDANI, et al.

SERIAL NO:

09/766,046

GAU:

2815

FILED:

January 19, 2001

EXAMINER: BAUMEISTER

FOR:

COMPLIANT SUBSTRATE

STRUCTURE AND METHOD FOR FABRICATING GAN DEVICES UTILIZING THE FORMATION OF A

# **INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97**

ASSISTANT COMMISSIONER FOR PATENTS WASHINGTON, D.C. 20231

SIR:

Applicant(s) wish to disclose the following information.

#### REFERENCES

- The applicant(s) wish to make of record the references listed on the attached form PTO-1449. Copies of the listed references were submitted in application Serial No. 09/908,888 according to the attached copy of a Granted Petition. This application contains related subject matter.
- A check is attached in the amount required under 37 CFR §1.17(p).

#### RELATED CASES

- ☐ Attached is a list of applicant's pending application(s) or issued patent(s) which may be related to the present application. A copy of the patent(s), together with a copy of the claims and drawings of the pending application(s) is attached along with PTO 1449.
- ☐ A check is attached in the amount required under 37 CFR §1.17(p).

# CERTIFICATION

- ☐ Each item of information contained in this information disclosure statement was first cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- □ No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

### **DEPOSIT ACCOUNT**

Please charge any additional fees for the papers being filed herewith and for which no check is enclosed herewith, or credit any overpayment to deposit account number 15-0030. A duplicate copy of this sheet is enclosed.

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Tel. (703) 413-3000 Fax. (703) 413-2220 (OSMMN 03/02)

Respectfully submitted,

SPIVAK, McCLELLAND.

Richard L. Treanor

Registration No. 36,379

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RADEMAR U.S. DEPARTMENT OF COMMERCE ATTY DOCKET NO. SERIAL NO. Form PTO 1449 (Modified) PATENT AND TRADEMARK OFFICE 206169US99 09/766,046 APPLICANT LIST OF REFERENCES CITED BY APPLICANT JAMAL RAMDANI ET AL FILING DATE GROUP JANUARY 19, 2001 2815 **U.S. PATENT DOCUMENTS** FILING DATE DOCUMENT DATE CLASS SUB **EXAMINER** NAME IF APPROPRIATE INITIAL NUMBER **CLASS** 04/09/74 AΑ 3,802,967 Ladany et al. AΒ 4,174,422 11/13/79 Matthews et al. AC 09/13/83 4,404,265 Manasevit 11/13/84 Hovel et al. ΔD 4,482,906 06/11/85 Morimoto et al. ΑE 4,523,211 AF 4,661,176 04/28/87 Manasevit 12/27/88 Meunier et al. AG 4,793,872 ÁΗ 4,846,926 07/11/89 Kay et al. 08/08/89 AJ 4,855,249 Akasaki et al. ΑI 4,891,091 01/02/90 Shastry 4,912,087 03/27/90 Aslam et al. ΑK ΑI 4,928,154 05/22/90 Umeno et al. 10/16/90 Wanlass et al. AΜ 4,963,949 08/25/92 AN 5,141,894 Bisaro et al. AO 5,159,413 10/27/92 Calviello et al. AΡ 5,173,474 12/22/92 Connell et al. 06/22/93 Chisholm et al. ΑQ 5,221,367 AR 5,225,031 07/06/93 McKee et al. ĀS 5,358,925 10/25/94 Neville Connell et al. 02/28/95 Summerfelt ΑT 5,393,352 5,418,216 05/23/95 Fork ΑU ΑV 09/19/95 McKee et al. 5,450,812 ΑW 5,478,653 12/26/95 Guenzer 5,482,003 01/09/96 McKee et al. 05/07/96 Nashimoto ΑY 5.514.484 ĀΖ 5,556,463 09/17/96 Guenzer Sheldon BA 5,588,995 12/31/96 BB 5,670,798 09/23/97 Schetzina 03/31/98 Fork et al. BC 5,733,641 04/07/98 Mantl et al. BD 5,735,949 BE 5,741,724 04/21/98 Ramdani et al. BF 09/22/98 Yano et al. 5,810,923 McKee et al. BG 5,830,270 11/03/98 Jia BH 5,912,068 06/15/99 02/01/00 Wollesen ы 6,020,222 ΒJ 6,045,626 04/04/00 Yano et al. ΒK 6,064,078 05/16/00 Northrup et al. 6,064,092 05/16/00 Park BL Ellis-Monaghan et al. ВМ 6,096,584 08/01/00 BN 6,103,008 08/15/00 McKee et al. 6,136,666 10/24/00 во ΒP 6,174,755 01/16/01 Manning BQ 6,180,486 01/30/01 Leobandung et al.

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				FILING DATE JANUARY 19, 2001		GROUP 2815	
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EVALUED		T DOOLINGHT		U.S. PATENT DOCUMENTS	CLASS	SUB	FILING DATE
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	CLASS	IF APPROPRIATE
	CA	3,766,370	10/16/73	Walther			
	СВ	4,006,989	02/08/77	Andringa			
	cc	4,284,329	08/18/81	Smith et al.			
	CD	4,777,613	10/11/98	Shahan et al.			
	CE	4,802,182	01/31/89	Thornton et al.			
	CF	4,882,300	11/21/89	Inoue et al.			, and the second
	CG	4,896,194	01/23/90	Suzuki			
4.000	СН	4,999,842	03/12/91	Huang et al.			
<u> </u>	СІ	5,081,062	01/14/92	Vasudev et al.			
	C1	.5,155,658	10/13/92	Inam-et-al.			
	СК	5,248,564	09/28/93	Ramesh			<u>-</u>
	CL	5,260,394	11/09/93	Tazaki et al.			
	СМ	5,270,298	12/14/93	Ramesh			
	CN	5,286,985	02/15/94	Taddiken			
	СО	5,310,707	05/10/94	Oishi et al.			
<u>.</u>	CP	5,326,721	07/05/94	Summerfelt			
	cq	5,404,581	04/04/95	Honjo			
	CR	5,418,389	05/23/95	Watanabe			
	cs	5,436,759	07/25/95	Dijaii et al.		-	
	СТ	5,576,879	11/19/96	Nashimoto			
	cu	5,606,184	02/25/97	Abrokwah, et al.		_	
	CV	5,640,267	06/17/97	May et al.			
	cw	5,674,366	10/07/97	Hayashi et al.		<del> </del>	
	СХ	5,729,641	03/17/98	Chandonnet et al.			
	CY	5,790,583	08/04/98	Ho			
	CZ	5,825,799	10/20/98	Ho et al.		<del> </del>	
	DA	5,857,049	01/05/99	Beranek et al.		+	
	DB	5,874,860	02/23/99	Brunel et al.		<del>                                     </del>	
	DC	5,926,496	07/20/99	Ho et al.			
	DD	5,937,285	08/10/99	Abrokwah, et al.			
<u>-</u>	DE	5,981,400	11/09/99	Lo			
	DF	5,990,495	11/23/99	Ohba			
	DG DG	6,002,375	12/14/99	Corman et al.		<u> </u>	
	DH	6,008,762	12/28/99	Nghiem			
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	DK	6,113,690	09/05/00	Yu et al.			
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	DM	6,121,642	09/19/00	Newns			
	DN	6,128,178	10/03/00	Newns			
	DO	6,143,072	11/07/00	McKee et al.			
	DP	6,184,144	02/06/01	Lo			
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EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	GA	4,868,376	09/19/89	Lessin et al.			
	GB	4,885,376	12/05/89	Verkade			
	GC	4,888,202	12/89	Murakami et al.			
	GD	4,891,091	12/90	Wanlass et al.			
	GE	5,051,790	09/24/91	Hammer			
	GF	5,055,445	10/08/91	Belt et al.			
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	GI	5,185,589	02/09/93	Krishnaswamy et al.			
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	GQ	5,371,734	12/06/94	Fischer			
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	GS	5,405,802	04/11/95	Yamagata et al.			
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	GX	5,473,171	12/95	Summerfelt			
	GY	5,479,033	12/26/95	Baca et al.			
	GZ	5,486,406	01/23/96	Shi			
	HA	5,491,461	02/13/96	Partin et al.			
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SHEET5 U.S. DEPARTMENT OF COMMERCE ATTY DOCKET NO. SERIAL NO. Form PTO 1449 CERADEMARY PATENT AND TRADEMARK OFFICE (Modified) 206169US99 09/766,046 APPLICANT LIST OF REFERENCES CITED BY APPLICANT JAMAL RAMDANI ET AL FILING DATE GROUP 2815 JANUARY 19, 2001 **U.S. PATENT DOCUMENTS** CLASS SUB FILING DATE DOCUMENT DATE NAME **EXAMINER** IF APPROPRIATE CLASS INITIAL NUMBER 07/22/97 5.650.646 Summerfelt ١A ΙB 08/12/97 5,656,382 Nashimoto 08/19/97 Shen et al. IC 5,659,180 D 5,661,112 08/26/97 Hatta et al. 11/95 Schetzina E 5.679.965 03/10/98 MacLeod 5,725,641 04/28/98 IG 5,745,631 Reinker 5,776,621 07/07/98 Nashimoto 07/07/98 Nakamura et al. 5,777,350 08/04/98 Wadaka et al. 5,789,845 IJ Sun-et-al. ΙĶ 5,792,569 08/1-1/98 5,792,679 08/11/98 Nakato 08/18/98 Kawakubo et al. lМ 5,796,648 09/01/98 Barber lιΝ 5,801,072 Ю 5,812,272 09/22/98 King et al. ΙP 5,814,583 09/98 ltozaki et al. Q 5,825,055 10/20/98 Summerfelt 10/27/98 Yonchara et al. 5,827,755 IR 11/10/98 Kovacs et al. IS 5,833,603 5,838,035 11/17/98 Ramesh 12/01/98 5,844,260 Ohori 12/08/98 Suh et al. 5,846,846 W 5,863,326 01/26/99 Nause et al. 02/16/99 lElla 5,872,493 5,879,956 03/99 Seon et al. Z 5,880,452 03/09/99 Plesko 03/16/99 Partin IΑ 5,883,564 05/25/99 JB 5,907,792 Droopad et al. JC 5,937,274 08/10/99 Kondow et al. JD 09/07/99 Kizuki 5,948,161 09/28/99 JF 5,959,879 Koo JF 10/99 Chen et al. 5,966,323 11/16/99 JG 5,987,011 Toh JΗ 6,022,140 02/08/00 Fraden et al. Ji 02/08/00 Yu et al. 6,022,410 6,023,082 02/08/00 McKee et al. JJ 02/22/00 Haartsen JK 6,028,853 JL 6,049,702 04/11/00 Tham et al. 06/20/00 Nashimoto et al JМ 6,078,717 07/00 JN 6,088,216 Laibowitz et al. 07/00 Laibowitz et al. IO 6,090,659 JΡ 6,107,721 08/22/00 Lakin JQ 6,153,010 11/28/00 Kiyoku et al

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ATTY DOCKET NO. 206169US99

SERIAL NO.

GROUP

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LISTO

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FILING DATE

**APPLICANT** 

JANUARY 19, 2001

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	ОВ	4,681,982	07/21/87	Yoshida			
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	OF	5,760,426	06/02/98	Marx et al.			
	OG	5,053,835	10/01/91	Horikawa et al.			
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	ОМ	5,312,765	05/17/94	Kanber			
	ON	5,734,672	03/31/98	McMinn et al.			
	00	6,367,699 B2	04/09/02	Ackley			
	OP	5,530,235	06/25/96	Stefik et al.			
	OQ	5,623,552	04/22/97	Lane			
	OR	5,481,102	01/02/96	Hazelrigg, Jr.			
	os	6,134,114	10/17/00	Ungermann et al.			
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	ΟU	5,789,733	08/04/98	Jachimowicz et al.			
	ov	5,753,300	05/19/98	Wessels et al.		. [	
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	QC	5,834,362	11/10/98	Miyagaki et al.			
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